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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/729,112	12/05/2003	Dapeng Wang	2269-3579.2US (98-0062.02	3169	
24247	7590 11/15/2005	EXAMINER		INER	
TRASK BRITT			ROSE, ROBERT A		
P.O. BOX 25	50				
SALT LAKE CITY, UT 84110			ART UNIT	PAPER NUMBER	
·			3723	3723	
		•	DATE MAN ED. 11/15/200	•	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
	10/729,112	WANG, DAPENG				
Office Action Summary	Examiner	Art Unit				
	Robert Rose	3723				
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the o	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPL' WHICHEVER IS LONGER, FROM THE MAILING D Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication If NO period for reply is specified above, the maximum statutory period of the specified period for reply within the set or extended period for reply will, by statute the Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tir will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE	N. nely filed the mailing date of this communication. ED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 24 A	<u>ugust 2005</u> .					
2a)⊠ This action is FINAL . 2b)□ This	This action is FINAL . 2b) This action is non-final.					
) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
4)⊠ Claim(s) <u>1-25 and 27-33</u> is/are pending in the application.						
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) <u>27-32</u> is/are allowed.						
-	6) Claim(s) <u>1-6,9,14-18,21 and 33</u> is/are rejected.					
_	7) Claim(s) 7,8,10-13,19,20 and 22-25 is/are objected to.					
8) Claim(s) are subject to restriction and/o	r election requirement.					
Application Papers						
9) The specification is objected to by the Examine	er.					
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11)☐ The oath or declaration is objected to by the Ex	kaminer. Note the attached Office	e Action or form PTO-152.				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of:						
1. Certified copies of the priority documents have been received.						
2. Certified copies of the priority documents have been received in Application No						
3. Copies of the certified copies of the priority documents have been received in this National Stage						
application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list	or the certified copies not receive	eu.				
Attachment(s)	_					
1) Notice of References Cited (PTO-892)	4) Interview Summary Paper No(s)/Mail D					
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 08/24/05. 		Patent Application (PTO-152)				
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DETAILED ACTION

Receipt is acknowledged of Applicant's Prior Art Statement, filed August 24,
 2005.

- 2. Claim 26 has been canceled.
- Claim 33 has been added.
- 4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 5. Claims 1-3, 6, 9, 14-15, 18, 21, and 33 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Breivogel et al. Breivogel et al disclose a cmp apparatus and method of polishing, comprising all of the subject matter set forth in Applicant's claims above. Note polishing pad(23); deformable pad(22)(20) having isolated solid supports(22); and ventral layer(20). The pad would inherently be expected to exhibit physical properties which vary with lateral distance across the pad, since the pad is not uniform throughout. For instance, resistance to a shear force would be expected to vary depending upon whether measurement is taken at a location above a solid region or above a void, as measurements are taken across the pad.
- 6. Claims 1, 3-6, 9, 14-18, 21, and 33 are rejected under 35 U.S.C. 102(a) as being anticipated by Eppert Jr. et al. Note figures 1-2 of Eppert Jr. et al which show a deformable layer comprised of a plurality of solid supports and an integral dorsal or

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ventral layer, corresponding to that shown in the embodiments of Applicant's figures 8 and 10. Note the use of a cushioning pad between the solid supports and the lower surface of the polishing pad. The pad of Eppert Jr. et al would inherently be expected to exhibit physical properties which vary with lateral distance across the pad, since the pad is not uniform throughout. For instance, resistance to a shear force would be expected to vary depending upon whether measurement is taken at a location above a solid region or above a void, as measurements are taken across the pad.

- 7. Claims 1-2, 9, 14, 21, and 33 are rejected under 35 U.S.C. 102(a) as being clearly anticipated by Tolles et al (US 6217426). Tolles et al discloses a CMP apparatus and method of polishing comprising all of the subject matter set forth in applicant's claims above. The pad of Tolles et al would inherently be expected to exhibit physical properties which vary with lateral distance across the pad, since the pad is not uniform throughout. For instance, resistance to a shear force would be expected to vary depending upon whether measurement is taken at a location above a solid region or above a void, as measurements are taken across the pad.
- 8. Claims 7-8, 10-13, 19-20, and 22-25 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 9. Claims 27-32 are allowed.
- 10. Applicant's arguments filed August 24, 2005 have been fully considered but they are not persuasive. Applicant's new limitation in the independent claims, of the pad exhibiting a physical property that varies across the deformable pad...parallel to the

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polishing surface, is deemed to be met by the art of record, for reasons set forth above. With regard to Applicants argument that the solid supports in Breivogel et al are not deformable, but are disclosed as rigid, the degree of deformability is not specified in the claim, and even supports comprised of an epoxy composition are subject to some degree of deformation. Moreover, Eppert, Jr. et al clearly shows a deformable pad(3) made up of solid supports, with integral ventral(fig.1), or dorsal(fig.2) layers, which are described as "semi-rigid", and which are located between the polishing pad and platen. Tolles et al also discloses deformable protrusions(60), which form a layer of solid supports which underlie the polishing pad(44).

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

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11. Any inquiry concerning this communication should be directed to Robert Rose at telephone number (571) 272-4494.

Rr

November 09, 2005

Robert Rose Primary Examiner Art Unit §723